

| | | | | | |
|--|--|--|--|---|--|
| INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i> | | Docket Number (Optional) TWI-31500 | | Application Number 09/938,415 | |
| | | Applicant(s) Kenneth C. Johnson et al. | | | |
| | | Filing Date August 23, 2001 | | Group Art Unit 2851 | |
| | | | | | |

U.S. PATENT DOCUMENTS

| *EXAMINER INITIAL | REF | DOCUMENT NUMBER | DATE | NAME | CLASS | SUBCLASS | FILING DATE |
|----------------------|-----|--------------------|------------|---------------|-------|----------|-------------|
| <i>AS</i> | AA | 5,867,276 | 02/02/1999 | McNeil et al. | 356 | 445 | 03/07/1997 |
| <i>AS</i> | AB | 5,963,329 | 10/05/1999 | Conrad et al. | 356 | 372 | 10/31/1997 |
| | | | | | | | |
| | | | | | | | |
| | | | | | | | |
| | | | | | | | |

FOREIGN PATENT DOCUMENTS

| REF | DOCUMENT NUMBER | DATE | COUNTRY | CLASS | SUBCLASS | TRANSLATION | |
|-----|--------------------|------|---------|-------|----------|-------------|----|
| | | | | | | YES | NO |
| | | | | | | | |
| | | | | | | | |
| | | | | | | | |
| | | | | | | | |

OTHER DOCUMENTS
(Including Author, Title, Date, Pertinent Pages, Etc.)

| | | |
|-----------|----|---|
| <i>AS</i> | AC | J. Allgair et al., "Manufacturing Considerations for Implementation of Scatterometry for Process Monitoring," <i>In Metrology, Inspection, and Process Control for Microlithography XIV, Proceedings of SPIE</i> , Vol. 3998 (2000), pp. 135-134. |
| <i>AS</i> | AD | J. Bao et al., "Specular Spectral Profilometry on Metal Layers," <i>In Metrology, Inspection, and Process Control for Microlithography XIV, Proceedings of SPIE</i> , Vol. 3998 (2000), pp. 882-892. |
| | | |
| | | |

| | |
|--|-----------------|
| Examiner | Date Considered |
| <i>AS</i> <i>9/23/04</i> | |
| Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | |